

Notice of References Cited	Application/Control No. 10/807,139	Applicant(s)/Patent Under Reexamination CHOI ET AL.	
	Examiner George A. Goudreau	Art Unit 1763	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-6,811,470	11-2004	Bonner et al.	451/41
*	B	US-6,776,810	08-2004	Cherian et al.	51/307
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

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	N	JP 2001-110,760	04-2001	Japan	Mizutari et. al.	-----
	O	JP 10-102,040	04-1998	Japan	Yoshida et. al.	-----
	P					
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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	"Effects of Nonionic Surfactants On Oxide-to-Polysilicon Selectivity During Chemical Mechanical Polishing"; Journal of the Electrochemical Society; 149 (8); (2002'); Lee et. al.; pp. 477-481
	V	
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	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.